

Sheet 1 of 1Substitute Form PTO-1449
(Modified)U.S. Department of Commerce
Patent and Trademark OfficeAttorney's Docket No.
05542-443001Application No.
09/903,052**Information Disclosure Statement
by Applicant**

(Use several sheets if necessary)

(37 CFR §1.98(b))

Applicant
Arkadiy Yampolskiy, et al.Filing Date
July 10, 2001Group Art Unit
3723**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
LW	AA	2001/015811	08/23/2001	Ravid, et al.			
	AB	2001/026364	10/04/2001	Ravid, et al.			
	AC	2002/005957	01/17/2002	Moshe, et al.			
	AD	5,486,129	01/23/1996	Sandhu, et al.			
	AE	5,658,183	08/19/1997	Sandhu, et al.			
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	AG	6,159,073	12/12/2000	Wiswesser, et al.			
	AH	6,261,152 B1	07/17/2001	Aiyer			
	AI	6,829,054 B2	12/00/2004	Stanke, et al.			
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
LW	AL	JP 9148284	06/06/1997	JP				
	AM	WO 99/25520	05/27/1999	WIPO				
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
LW	AQ	Pan, J. Tony, et al., "Copper CMP and Process Control," Final Paper submitted to CMP-MIC Conference, February 11-12, 1999, Santa Clara, CA and Cambridge, MA, 7 pp.
	AR	Ravid, Avi, et al., "Copper CMP Planarity Control Using ITM," IEEE/SEMI Advanced Semiconductor Manufacturing Conference, 2000, pp. 437-443.
	AS	
	AT	

Examiner Signature

Date Considered

4/13/06

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute Disclosure Form (PTO-1449)